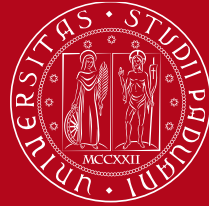


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XUV spectroscopy for space (SOLAR-C EUVST) and laboratory applications



Gabriele Zeni - 37th Cycle

Supervisor: Dr. Lorenzo Cocola

Co-supervisor: Prof. Giampiero Naletto

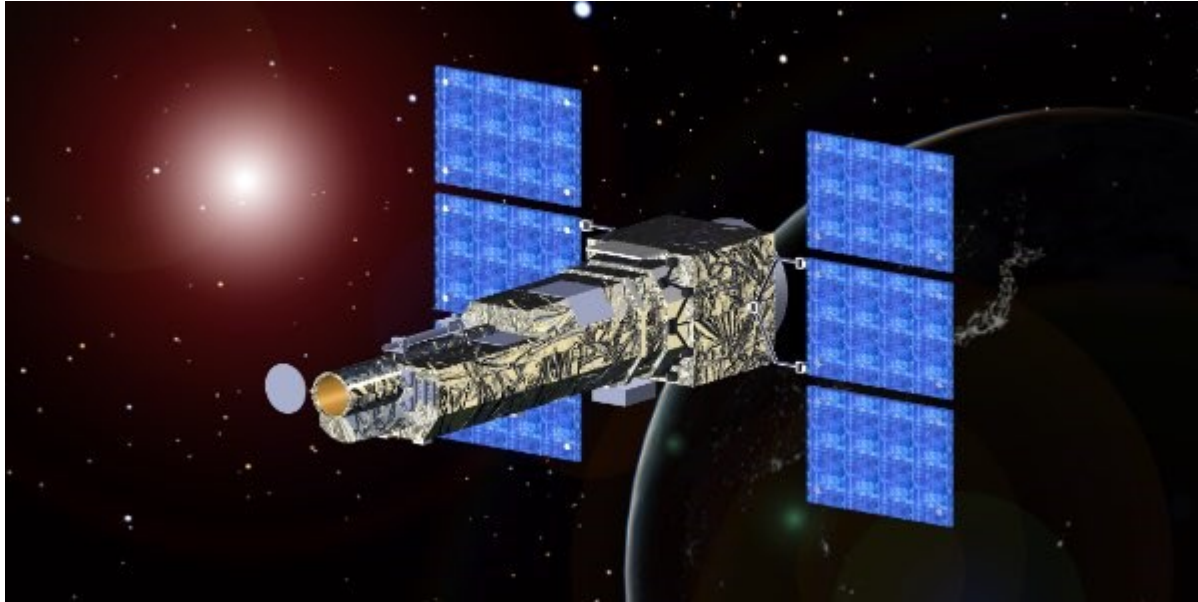
Dr. Luca Poletto

Dr. Fabio Frassetto

Admission to thesis evaluation - 13/09/2023

Summary

- XUV spectroscopy for Space application: **SOLAR-C/EUVST**
- XUV spectroscopy for Laboratory application: **XUV bendable grating**
- XUV spectroscopy for Laboratory application: **COSP**



XUV spectroscopy for Space application: **SOLAR-C/EUVST**

SOLAR-C_EUVST

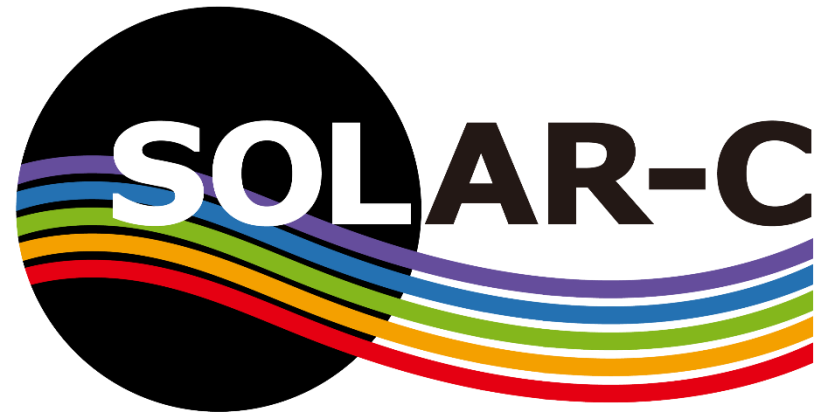
Extreme UltraViolet High-Throughput Spectroscopic Telescope

JAXA M-class mission

International participation

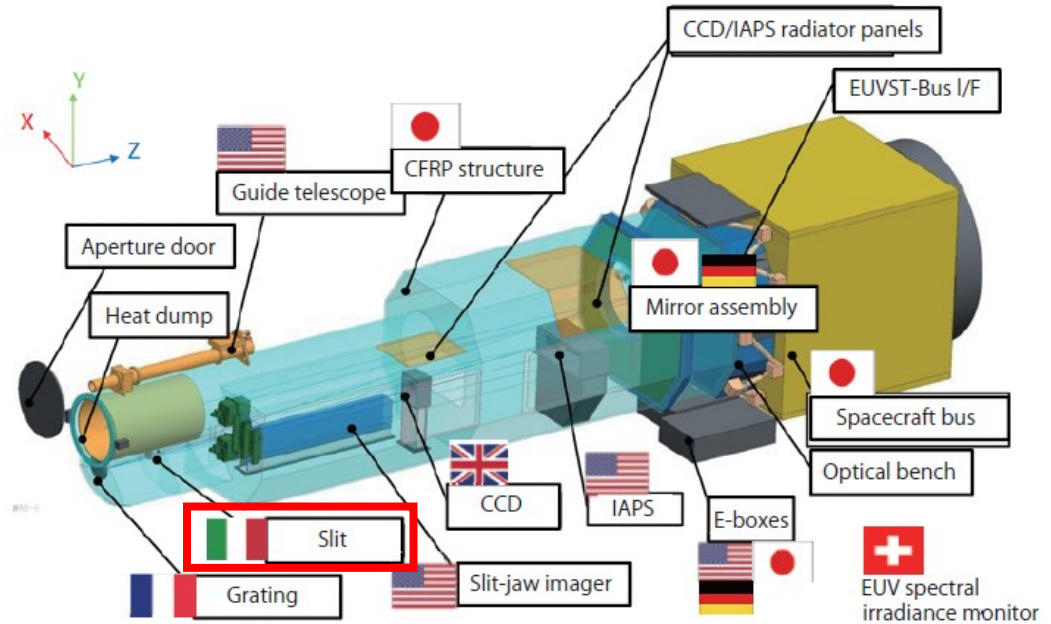
Purpose: to understand

- Formation of solar atmosphere and solar wind
- Instabilities of the solar atmosphere



INAF (Istituto Nazionale di Astrofisica) is responsible for the realization of the Slit Assembly

CNR-IFN will perform the calibration of the Slit Assembly



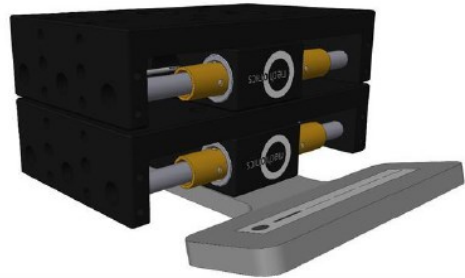
Slit Assembly

Limit the light entering the
imaging spectrograph

- 4 scientific slits
- 1 calibration slit
- 1 pinhole
- 1 circular aperture
- stop position



Reflect light onto the
Slit-Jaw Imager



Positioner: two
linear translators
(piezo-actuator)

Redundancy and
efficiency

with Lorenzo Cocola, Luca Poletto

Preliminary theoretical analysis of the Slit Assembly coating

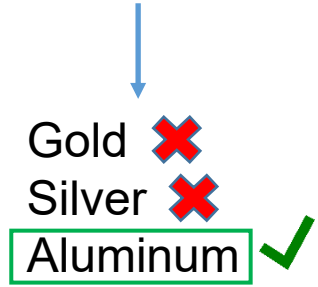
High solar input on thin substrate \longrightarrow Coating to reduce heat absorption

Coating requirements:

- High reflectivity, especially in 280 nm band
- Not exceed 600 nm thickness

Coating	N7419	N7420	N7421	N7422	P3157	P3158
Solar absorbance α	0.254	0.322	0.396	0.175	0.560	0.603
Solar flux absorption by PM (W)	22.22	28.20	34.68	15.33	48.96	52.76
Reflected Solar flux (W)	65.27	59.29	52.82	72.16	38.53	34.73
Solar flux input on slit (W)	4.64	4.22	3.75	5.13	2.74	2.47

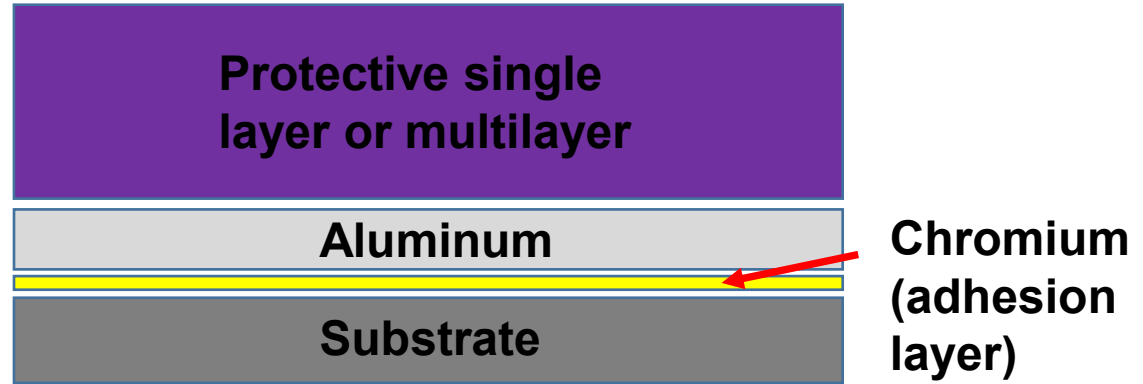
Metal-based coating



Needs protective layer

Protected Al coating

- Single-layer protected Al coating
- Multilayer protected Al coating

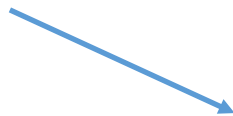


Single-layer protected Al coating

- Simple (single layer of SiO_2 or MgF_2)
- Not so efficient

Multilayer protected Al coating

- Complex (fully dielectric multilayer)
- Very efficient



Theoretical analysis of several coating structures:

- SiO_2/Al and MgF_2/Al single layer
- $[\text{MgF}_2/\text{SiO}_2]^3/\text{Al}$; $[\text{Al}_2\text{O}_3/\text{SiO}_2]^3/\text{Al}$; $[\text{TiO}_2/\text{SiO}_2]^3/\text{Al}$ and $\text{SiO}_2/[\text{ZrO}_2/\text{SiO}_2]^3/\text{Al}$ multilayer

A genetic algorithm is prepared to optimize the thickness of each single layer
Another algorithm calculates the absorbed heat

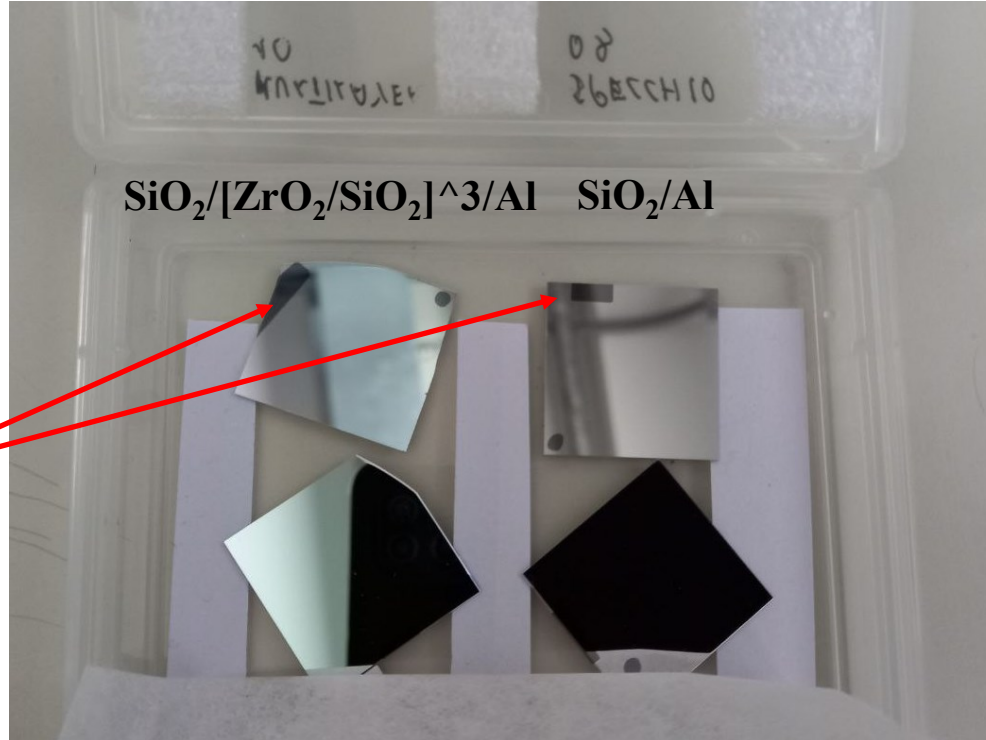
N7422 Primary Mirror Coating

Slit coating	Absorbed Heat (250-1700 nm)	Reflected Heat
Bare Al (reference)	0.357 W	4.213 W
Al + single layer [SiO ₂ or MgF ₂]	0.467 W	4.103 W
[Al ₂ O ₃ /SiO ₂]/Al, 6 layers	0.386 W	4.184 W
[ZrO ₂ /SiO ₂]/Al, 7 layers	0.363 W	4.207 W

Label	Structure	Total thickness
[ZrO ₂ /SiO ₂] / Al, 7 layers	SiO ₂ (40 nm)	523 nm
	ZrO ₂ (74 nm)	
	SiO ₂ (82 nm)	
	ZrO ₂ (25 nm)	
	SiO ₂ (32 nm)	
	ZrO ₂ (90 nm)	
	SiO ₂ (80 nm)	
	Al (90 nm)	
	Cr (10 nm) – adhesion layer	

Label	Structure	Total thickness
SiO ₂ /Al, single layer	SiO ₂ (257 nm)	357 nm
	Al (90 nm)	
	Cr (10 nm) – adhesion layer	

Measurements of the optical properties and thickness of the coating samples



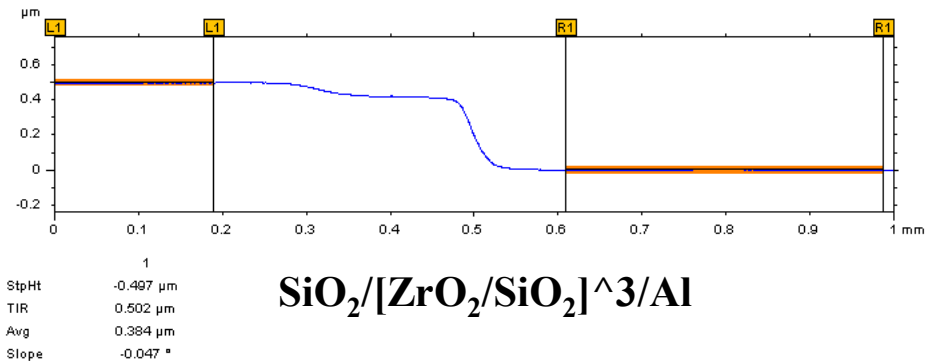
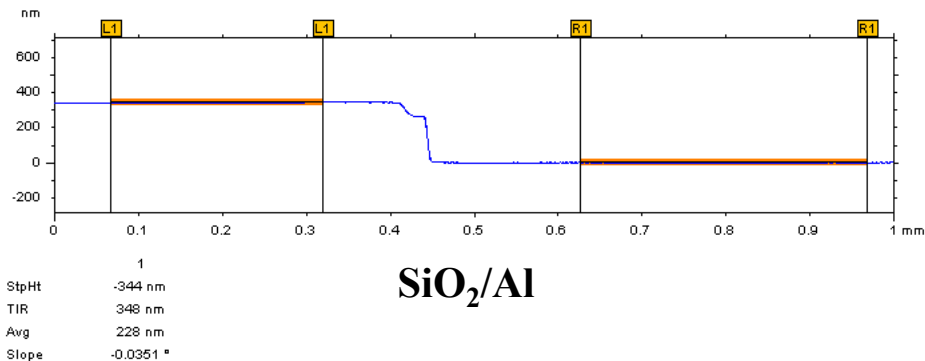
Clamped area
Bare substrate
used for
thickness
measurements

Measurements
campaign:

- Profilometric analysis
- **Reflectance analysis**

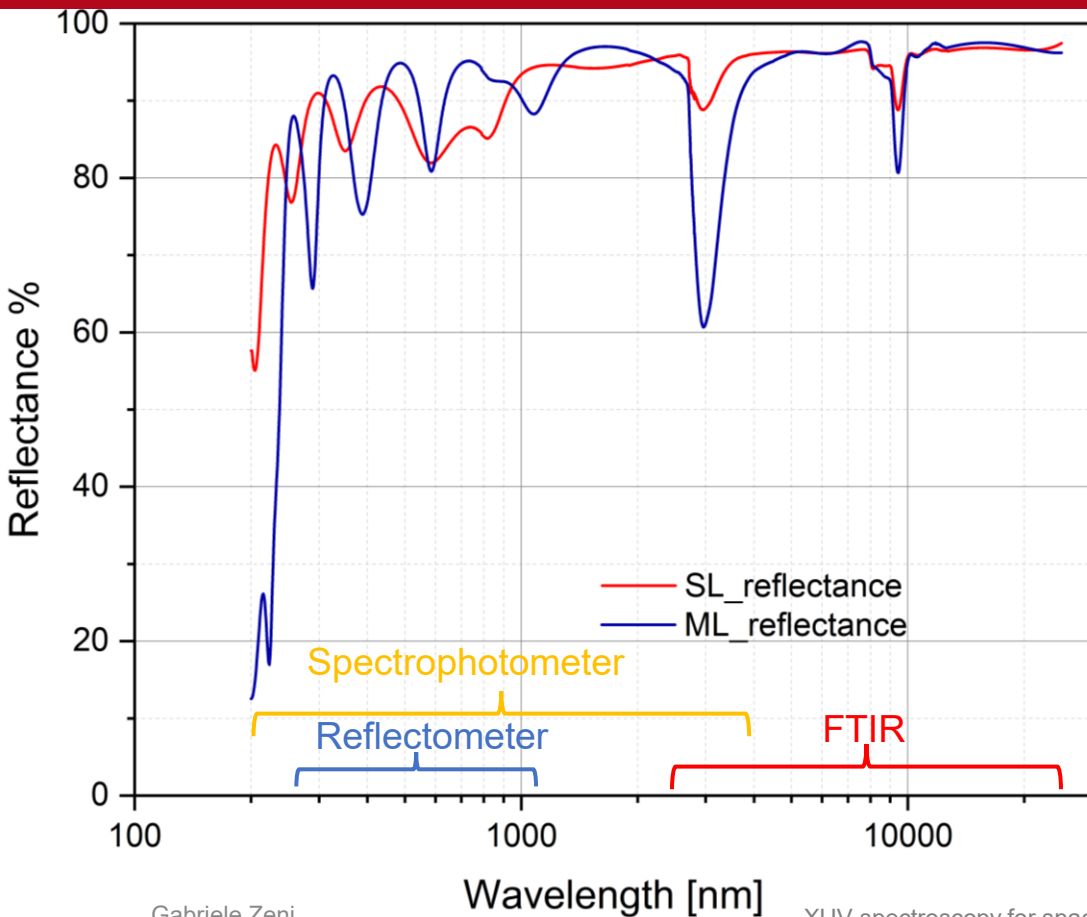


Reflectometer
Spectrophotometer
FTIR spectrometer



	Theoretical thickness	Measured thickness	Error
Single layer	357 nm	344 nm	3.8%
Multilayer	523 nm	497 nm	5.2%

Small deposition error, compatible with the intrinsic precision of the deposition process



Complete reflectance measurements, from the near UV (200 nm) to the mid IR (25 μ m)

Three partially overlapped measured region:

- **Reflectometer:**
300 – 1100 nm
- **Spectrophotometer:**
200 – 3000 nm
- **FTIR spectrometer:**
2500 – 25000 nm

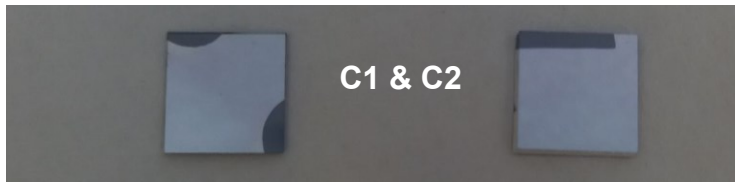
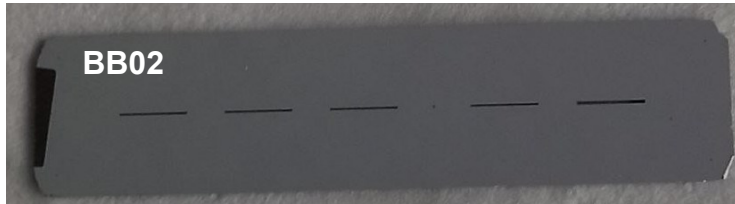
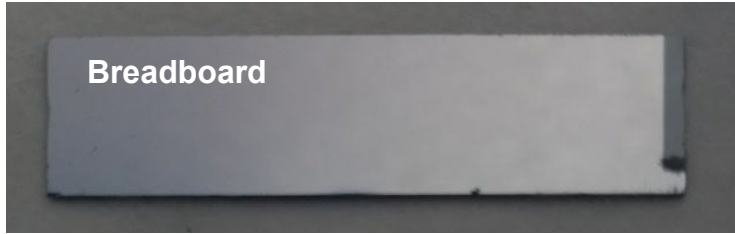
Absorbed heat, calculated using the measured sample reflectance
In the case of P3157, using also the reflectance measured by MPS

P3157 Primary Mirror Coating

Slit coating	Absorbed Heat (250-2500 nm)
SiO ₂ /Al	0.2659 W
[ZrO ₂ /SiO ₂]/Al, 7 layers	0.2133 W

N7422 Primary Mirror Coating

Slit coating	Absorbed Heat (250-2500 nm)
SiO ₂ /Al	0.5290 W
[ZrO ₂ /SiO ₂]/Al, 7 layers	0.4248 W



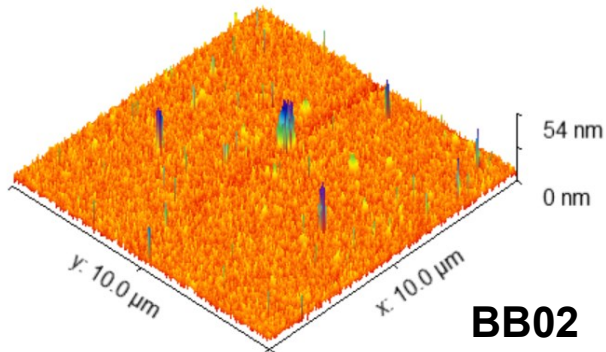
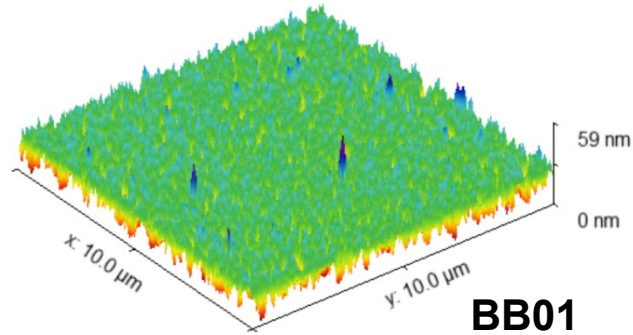
First prototype samples of the Slit Assembly

- Si substrate
- $[\text{SiO}_2]/\text{Al}$ optical coating

Test:

- Surface roughness
- Surface reflectivity
- Surface planarity

AFM (Atomic Force Microscope) to evaluate the surface roughness



Five areas of 10x10 μm for each sample

Sample	Roughness RMS
BB 01	1.906 nm
BB 02	1.911 nm
Breadboard	1.621 nm
C1	1.604 nm
C2	1.798 nm

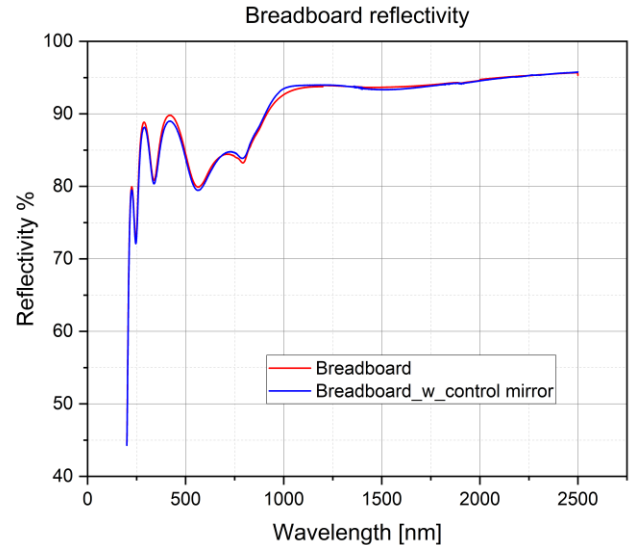
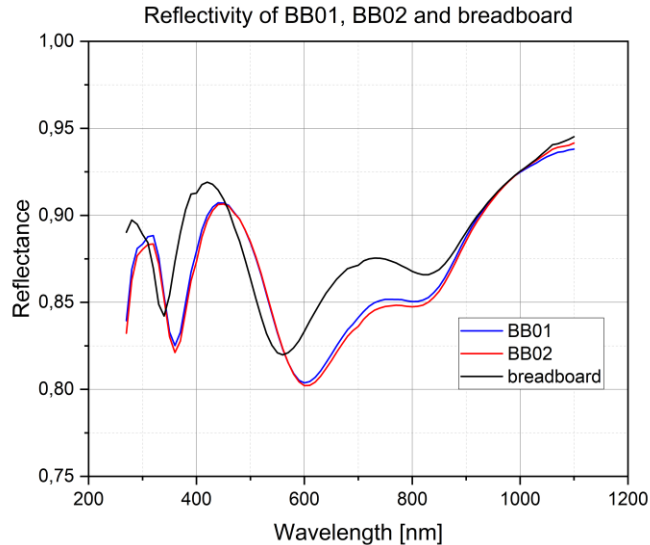
Slightly larger for slit samples, probably due to chemical etching prior to the deposition (under investigation)

Reflectivity: reflectometer + spectrophotometer

The spectrophotometer allows only the breadboard sample due to beam dimension

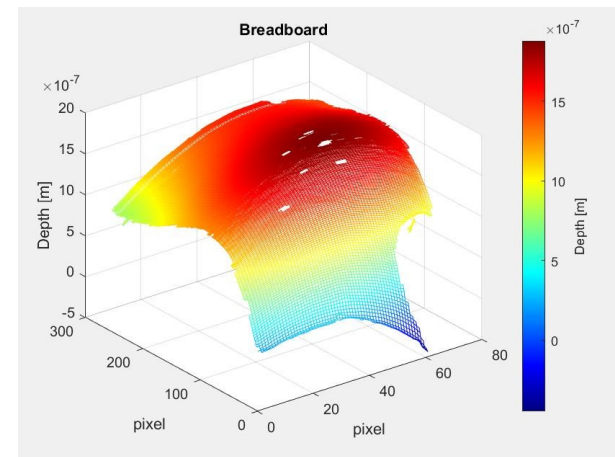
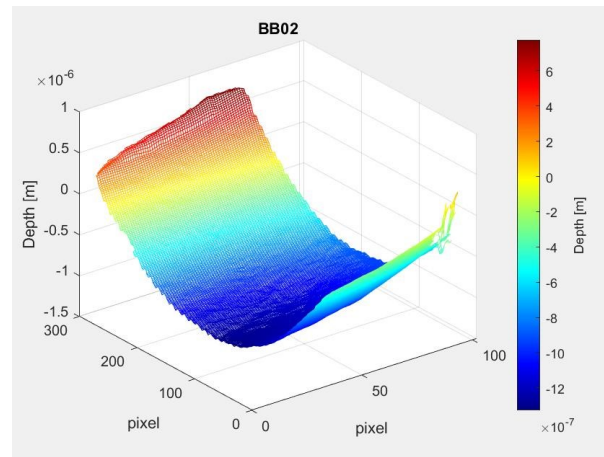
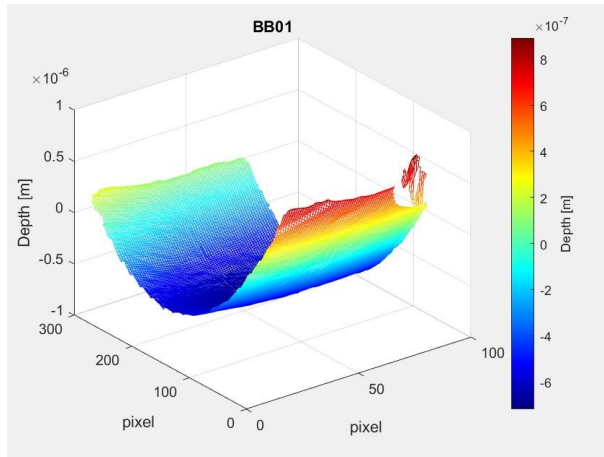
Comparable reflectivity (within the instrumental error $\pm 2\%$)

Bentham Reflectometer



Cary Spectrophotometer

Zygo Interferometer → Interferogram to evaluate the planarity



Almost cylindrical small curvature on the long size, less than $\approx 2 \mu\text{m}$ peak-to-valley
 In small 6x6 mm region, equivalent to the FoV, the curvature is $< 200 \text{ nm}$, well below the requirement

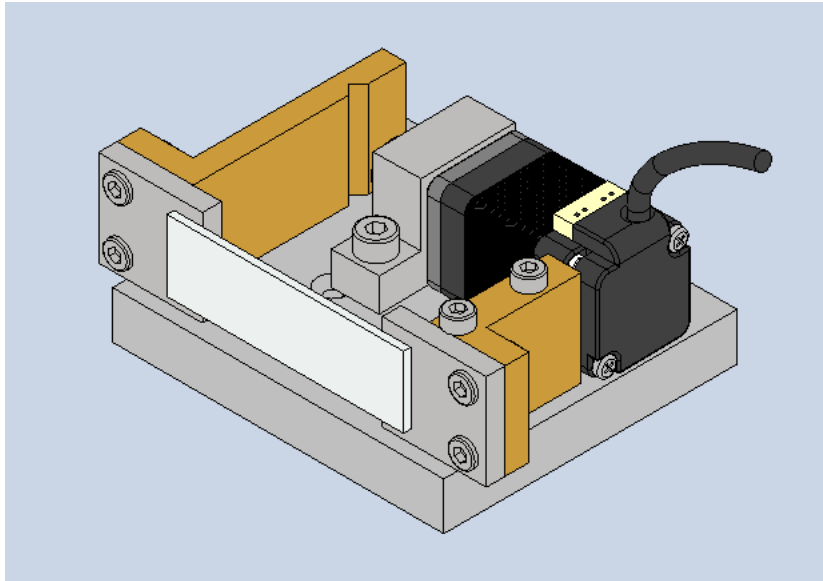
The study has been shared with other EUVST teams and it has been presented at the ICSO 2022 conference and at the SPIE 2024 conference

Zeni G. *et al.*, **Multilayer coating analysis for heat rejection on the Slit Assembly of SOLAR-C EUVST**, Proc. of SPIE Vol. 12777, Conference Paper, Jul 2023

Zeni G. *et al.*, **Reflectivity analysis of a proposed multilayer coating for the Slit Assembly of SOLAR-C EUVST**, Proc. of SPIE Vol. 13100, Conference Paper, Aug 2024

Next steps:

- Development of a calibration technique to evaluate the impact of the solar flux onto the SA when mounted on its frame

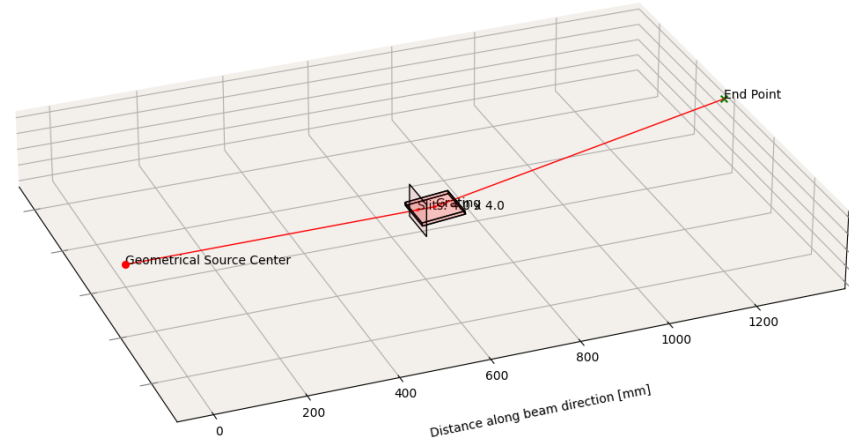
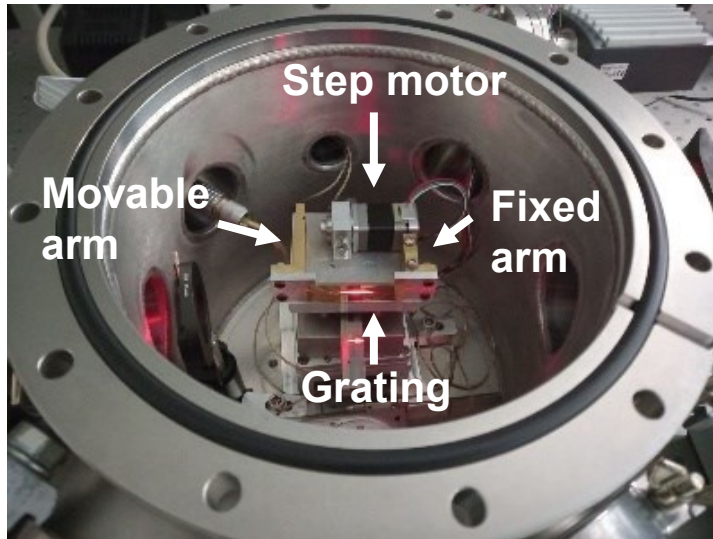


XUV spectroscopy for Laboratory application: **XUV bendable grating**

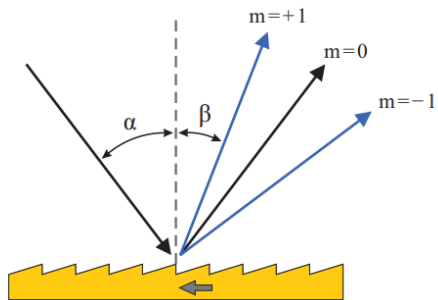
with Fabio Frassetto, Luca Poletto

Focusing test of XUV deformable grating

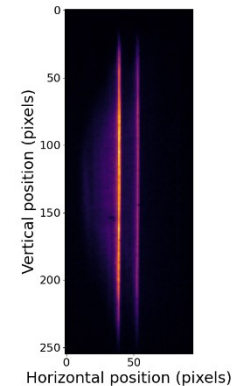
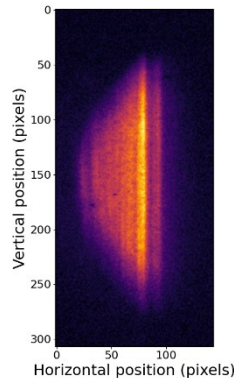
Deformable grating could be used in monochromator, reducing the amount of optical elements



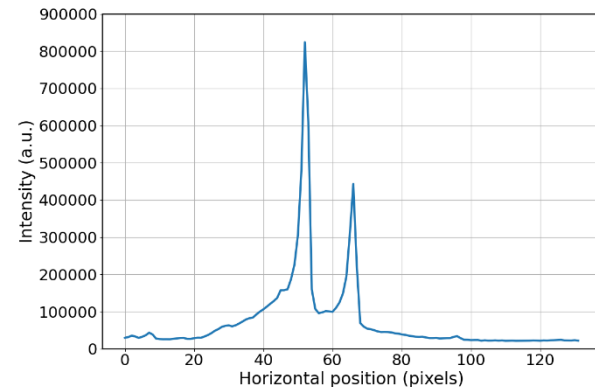
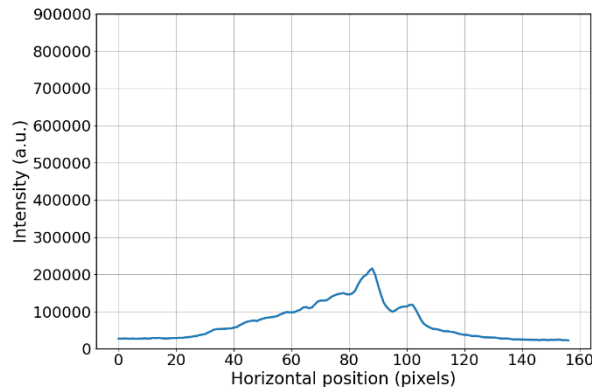
Test with He and Ne,
three lines each, both
with the blaze arrow of
the grating toward the
source and toward the
camera



Gabriele Zeni



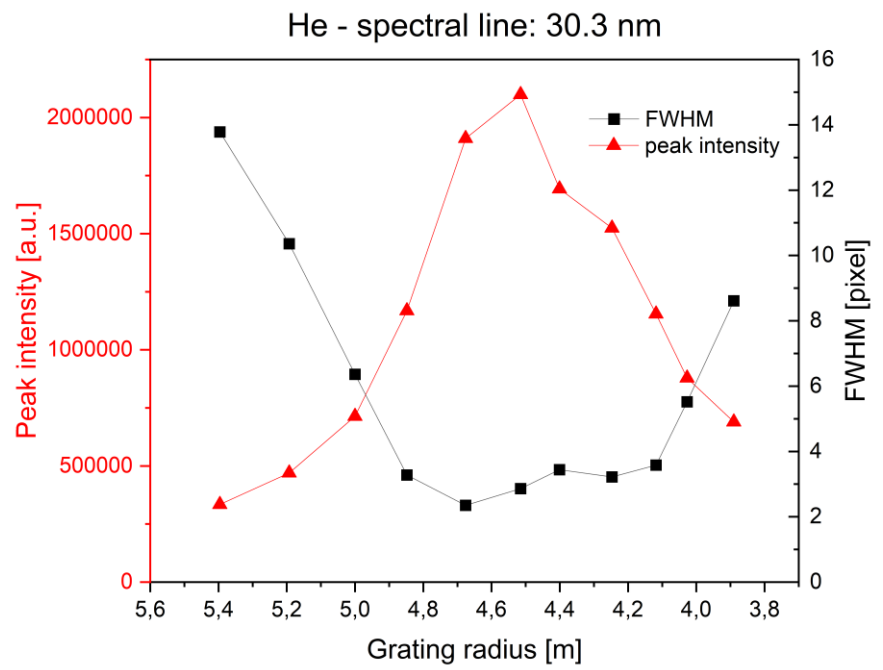
Ne 74.0 nm
doublet



Plot the FWHM and the peak intensity



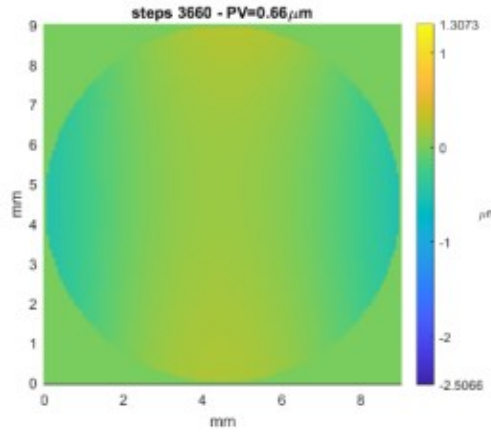
Obtain the bending radius for the in-focus position



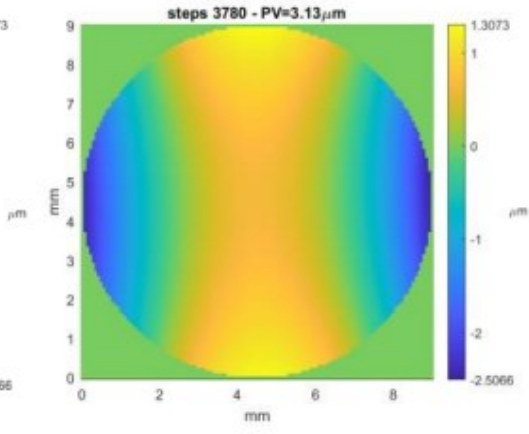
Shack-Hartmann wavefront sensor (WFS) analysis



To analyze the shape of the deformation

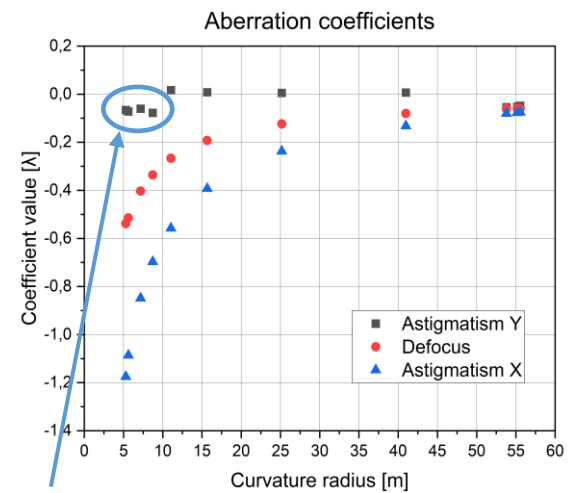


R = 50 m



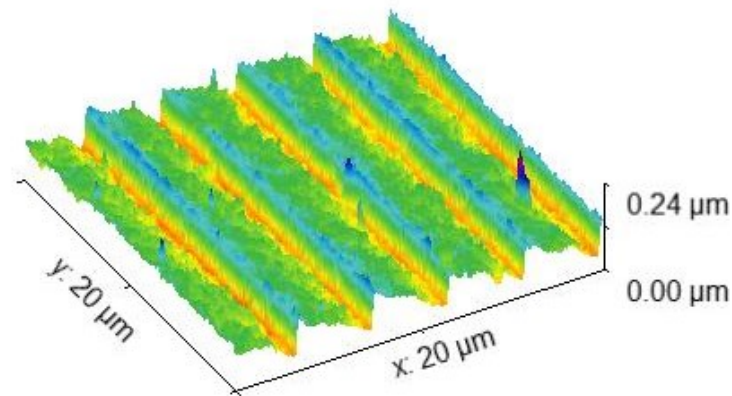
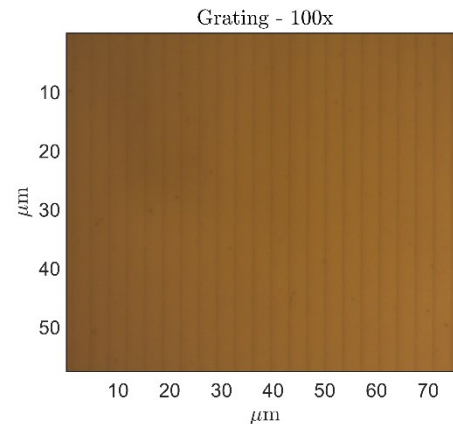
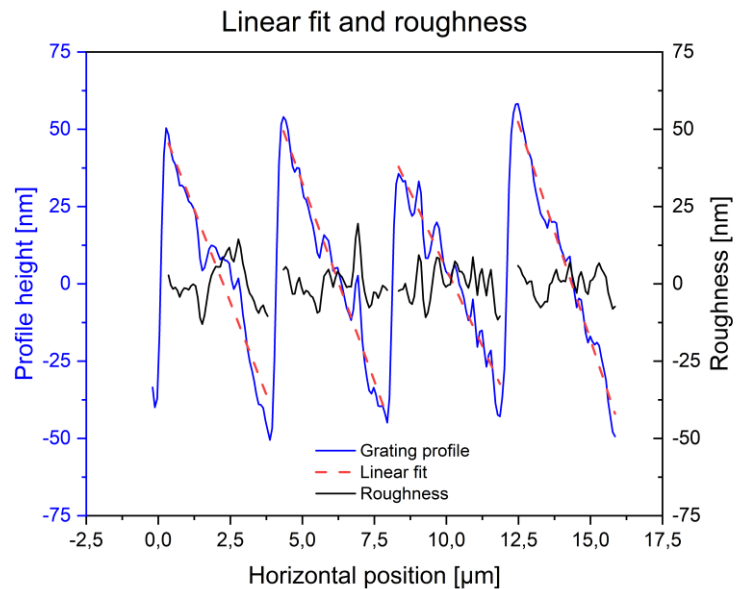
R = 5 m

Almost pure cylindrical deformation



Very little residual sagittal astigmatism: unwanted torsional deformation

Optical microscope surface analysis AFM surface and roughness analysis



Results:

- Fully working mounting frame
- Complete bending test of the deformable grating
- Complete analysis of the grating surface

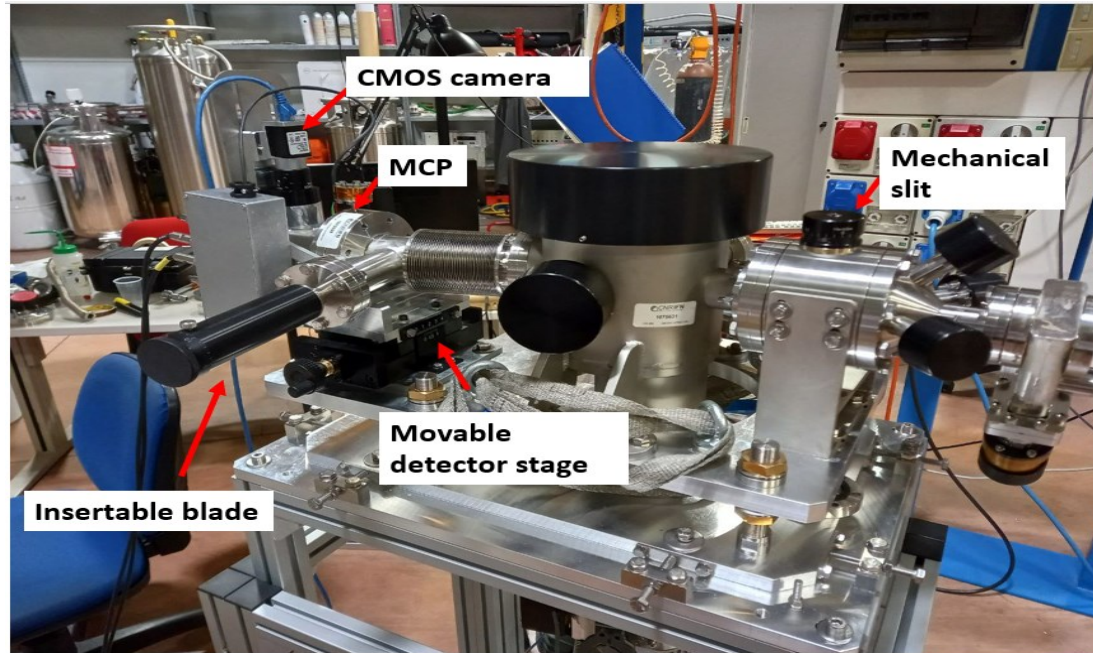
The study has been presented at the SPIE Optics and Optoelectronics Conference in Prague, April 2023 and the AOIM – Adaptive Optics for Industry and Medicine in Padua, March 2024

Zeni G. *et al.*, **Bendable grating for monochromatization in the extreme-ultraviolet**, Proc. of SPIE Vol. 12581, Conference Paper, June 2023

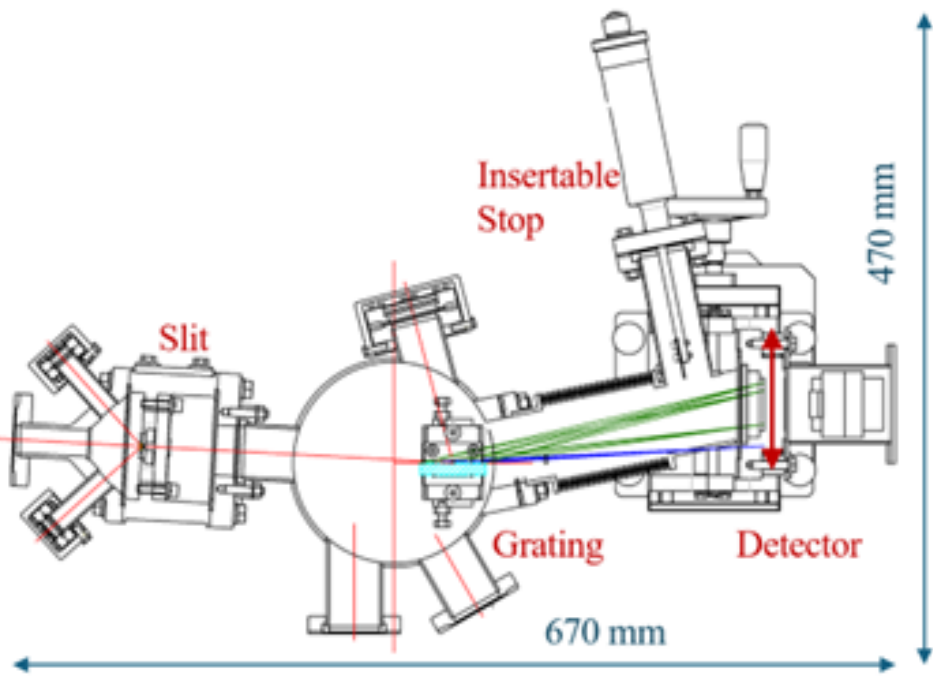
Zeni G. *et al.*, **Monochromatization in the EUV region with a low-cost active grating**, Adaptive Optics for Industry and Medicine XIII

Next steps:

- Possible development of a complete two stage bendable grating instrumentation



XUV spectroscopy for Laboratory application: **COSP**



COmpact SPectrometer – COSP

Grating spectrometer for FEL application

Achieve medium resolution in a **wide spectral range**

For:

- Optimizing of the machine parameters
- Monitoring of the harmonics stability

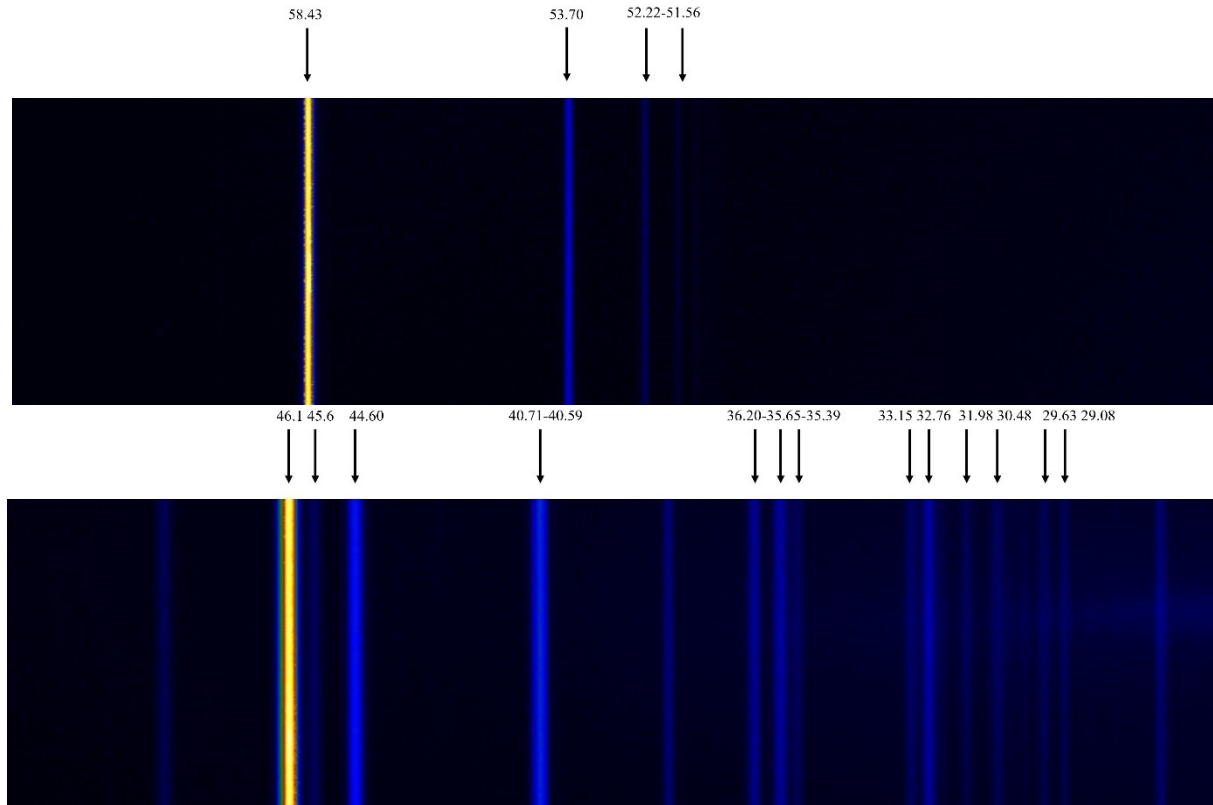
Calibration and commissioning activities

Hollow cathode lamp

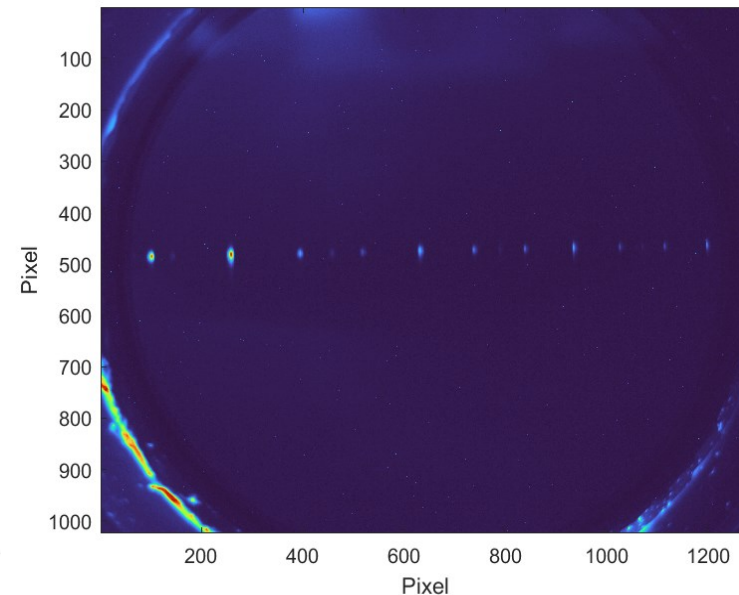
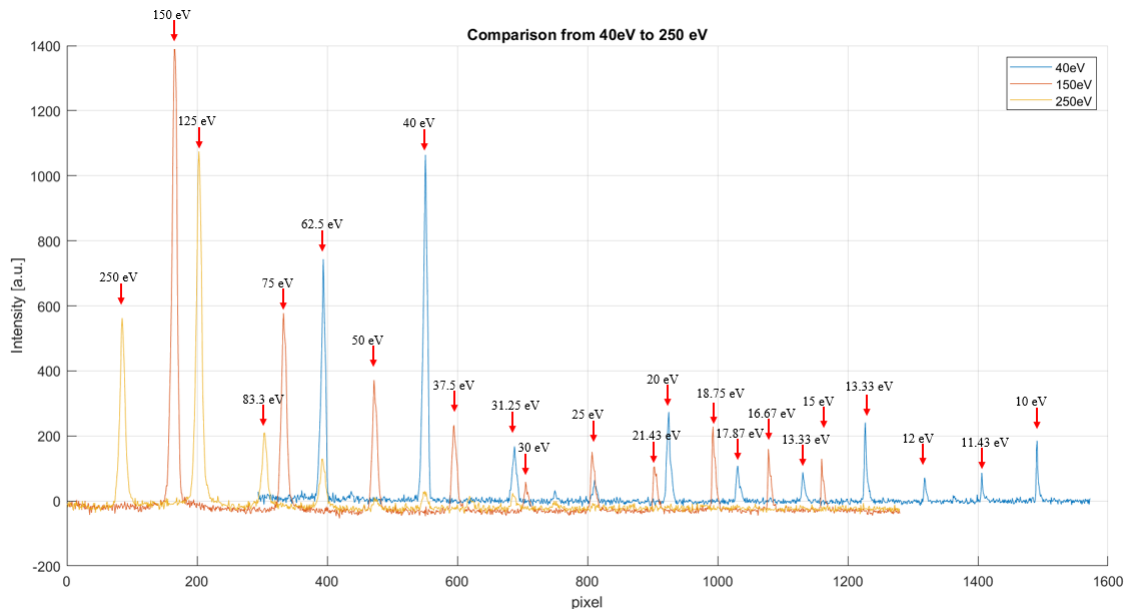
- He I lines
- Ne II lines

Observation and identification of the spectral lines

Confirm the grating alignment and dispersive capabilities



Test with CiPo – Circular Polarization beamline Energies from 40 eV to 250 eV (20 nm to 5 nm)



From the position of the signal onto the detector (pixel position)

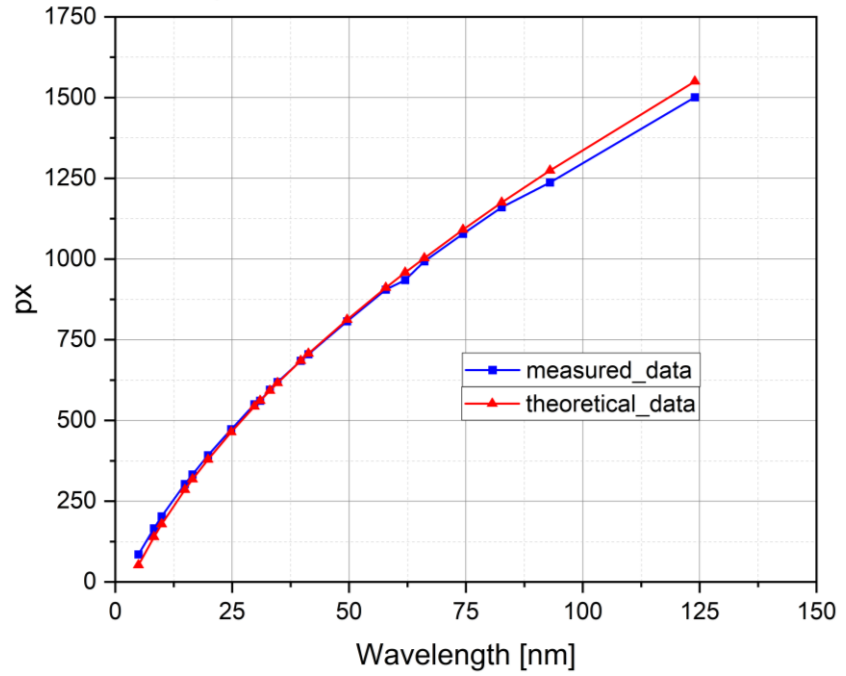


Polynomial fit

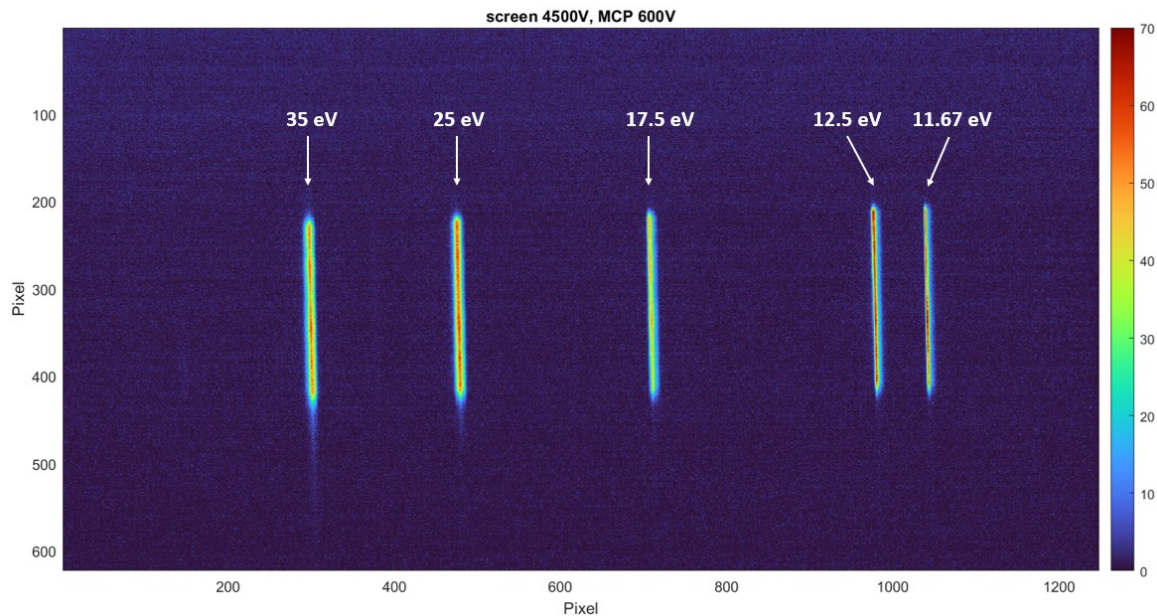
$$y = -a + b * \lambda - c * \lambda^2 + d * \lambda^3 - e * \lambda^4 + f * \lambda^5 - offset / 0.033$$

If the energy is unknown, the position on the detector gives the signal energy

Comparison measured data and theoretical data

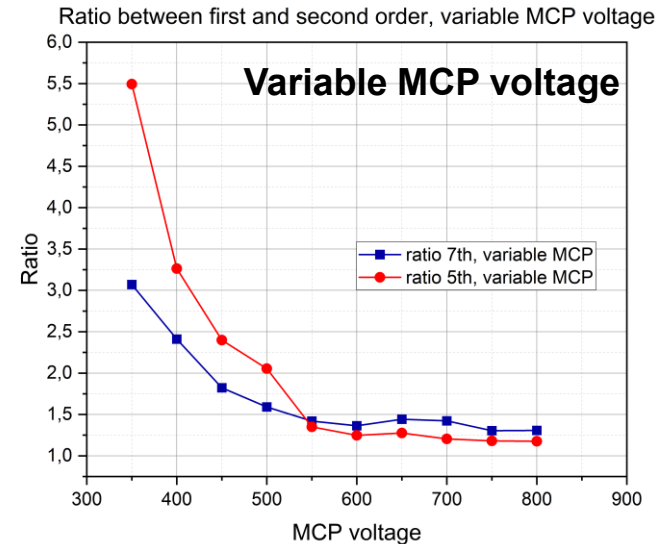
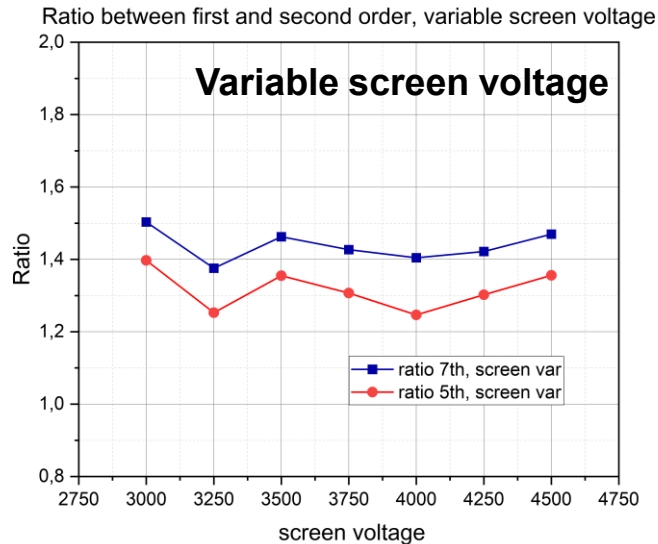


Test at FERMI LDM – **Low Density Matter** beamline of the free electron laser
Two harmonics, 7th and 5th (35 and 25 eV) and their second order
Variable MCP and screen voltage to test the linearity of the system

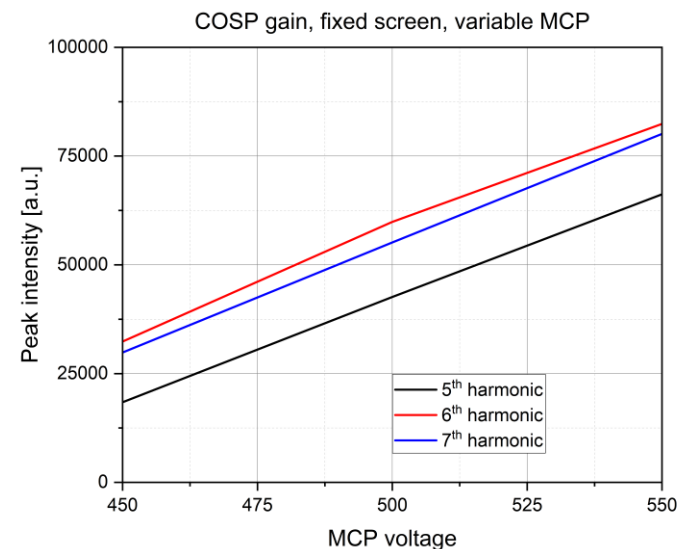
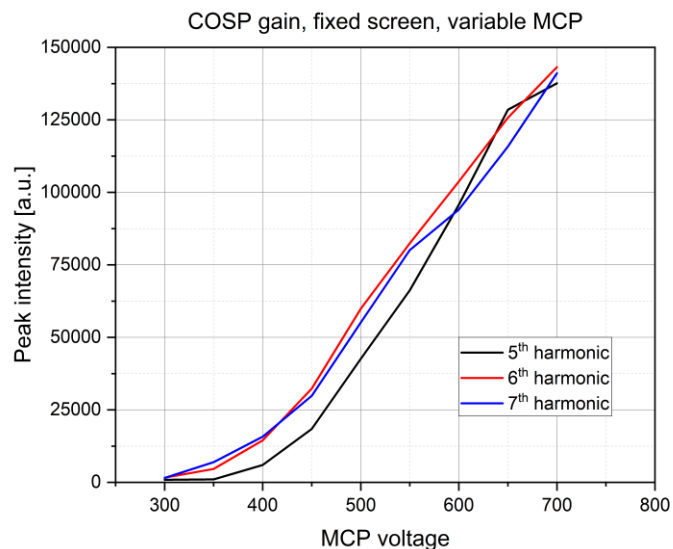


Ratio between first and second order at different MCP and screen voltage

- Screen voltage: no effect on linearity
- MCP voltage: **high level of non-linearity**



Three harmonics (7th, 6th and 5th) with fixed screen and variable MCP voltage
Region of linear gain: **450-550 V for the MCP**



Results:

- Successful commissioning of the COSP
- First tests of COSP during the preparatory phase of an experiment by prof. Sansone (Freiburg University)

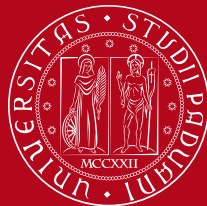
The results have been presented at the SRI 2024 Conference in Hamburg, Aug 2024

Zeni G. *et al.*, **COSP: a dedicated compact wide-band spectrometer for free-electron-laser monitoring**, under submission to Photonics Journal

Thanks for the attention



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The logo for the 800th anniversary of the University of Padua, featuring a large '800' with 'ANNI' underneath and the years '1222 • 2022' above it.

UNIVERSITÀ
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DI PADOVA

The text 'UNIVERSITÀ DEGLI STUDI DI PADOVA' in a white, serif font, arranged in three lines.



- Collaboration in research activities at CNR-IFN lab, especially characterization of optical space elements operating in the UV and visible band
- Collaboration in the research activities about deformable grating and satellite instrumentation for the EUV observation
- Study of the reflectivity of mirror coatings in the UV band



MAX PLANCK INSTITUTE
FOR SOLAR SYSTEM RESEARCH

with Udo Schuehle, Luca Teriaca

From January 2023 to June 2023: in Max Planck Institute for Solar System Research in Gottingen

Preliminary analysis of the reflectance stability of the PMA coating at variable temperatures

Temperature	Reflectance at 121.6 nm
22° C	37.7 %
60° C	37.8 %
100° C	37.9 %
100° C (after 18 hours)	37.8 %
120° C	38.5 %

